

	Hits	Search Text	DBs
2	3	((microstructure or microlens\$4 or (len\$3 near6 array)) near12 (substrate or wafer or device or workpiece or platen or drum) near22 ((form\$4 or deposit\$4 or coat\$4 or apply\$3 or application) near12 (resist or (radiation near5 sensitive) or photoresist or photosensitive)) same (imping\$4 or expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4 same (radiation or laser or UV or DUV or EUV)) and ((photoresist or resist or photosensitive) same negative) and ((microstructure or microlens\$4 or (lens\$2 near9 array)) same (non\$4uniform\$4 or variable or vary\$4 or non\$4planar))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
3	24	((microstructure or microlens\$4 or (len\$3 near6 array)) near12 (substrate or wafer or device or workpiece or platen or drum) near22 ((form\$4 or deposit\$4 or coat\$4 or apply\$3 or application) near12 (resist or (radiation near5 sensitive) or photoresist or photosensitive)) near25 (imping\$4 or expos\$4 or irradiat\$4 or illuminat\$4) near22 develop\$4 near22 (radiation or laser or UV or DUV or EUV))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
4	50	((microstructure or microlens\$4 or (len\$3 near6 array)) near12 (substrate or wafer or device or workpiece or platen or drum) near22 ((form\$4 or deposit\$4 or coat\$4 or apply\$3 or application) near12 (resist or (radiation near5 sensitive) or photoresist or photosensitive)) same (imping\$4 or expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4 same (radiation or laser or UV or DUV or EUV))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
5	1	"20040146807"	US-PGPUB; USPAT
6	3	((("20040146807") or ("20030224253") or ("6746823"))).PN.	US-PGPUB; USPAT
7	19	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or gate) near12 (substrate or wafer or device or workpiece or platen or drum or (flexible near5 substrate) or elastomeric) near22 ((form\$4 or deposit\$4 or coat\$4 or apply\$3 or application) near12 (resist or (radiation near5 sensitive) or photoresist or photosensitive)) same (imping\$4 or expos\$4 or irradiat\$4 or illuminat\$4) same (radiation or laser or UV or DUV or EUV)) and (stamper or (master near12 mold))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
8	3	((("6043001") or ("20040047014") or ("20020048729"))).PN.	US-PGPUB; USPAT

	Hits	Search Text	DBs
9	1	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or gate or pattern) near12 (substrate or wafer or web) near16 (drum or (cylind\$5 near9 platform\$3)) near22 ((form\$4 or deposit\$4 or coat\$4 or apply\$3 or application) near12 (resist or (radiation near5 sensitive) or photoresist or photosensitive)) same (imping\$4 or expos\$4 or irradiat\$4 or illuminat\$4) same (radiation or laser or UV or DUV or EUV))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
10	1	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or gate or pattern) near26 (substrate or wafer or web) near35 (drum or (cylind\$5 near9 platform\$3)) near32 ((form\$4 or deposit\$4 or coat\$4 or apply\$3 or application) near22 (resist or (radiation near5 sensitive) or photoresist or photosensitive))) and ((resist or photoresist or photocur\$4 or photosensitive) same (imping\$4 or expos\$4 or irradiat\$4 or illuminat\$4) same (radiation or laser or UV or DUV or EUV) same develop\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	18	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or structure or pattern) same (substrate or wafer or web) same (drum or (cylind\$5 near9 platform\$3)) same (resist or (radiation near5 sensitive) or photoresist or photosensitive or photocur\$4)) and ((resist or photoresist or photocur\$4 or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4) and ((resist or (radiation near5 sensitive) or photoresist or photosensitive) same (thickness or amount) same (topograph\$4 or surface or layer or film) same (non\$4uniform or variable or vary\$4 or non\$4planar))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	10	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or gate or pattern) same (substrate or wafer or web) same (drum or (cylind\$5 near9 platform\$3)) same ((form\$4 or deposit\$4 or coat\$4 or apply\$3 or application) near32 (resist or (radiation near5 sensitive) or photoresist or photosensitive))) and ((resist or photoresist or photocur\$4 or photosensitive) same (imping\$4 or expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4) and ((resist or (radiation near5 sensitive) or photoresist or photosensitive) same (thickness or topograph\$4 or surface) same (non\$4uniform or variable or vary\$4 or non\$4planar))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
13	14	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or structure or pattern) same (substrate or wafer or web) same (drum or (cylind\$5 near9 platform\$3)) same (resist or (radiation near5 sensitive) or photoresist or photosensitive or photocur\$4)) and ((resist or photoresist or photocur\$4 or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4) and ((resist or (radiation near5 sensitive) or photoresist or photosensitive) same thick\$4 same (topograph\$4 or surface or layer or film) same (uneven or non\$4uniform or variable or vary\$4 or non\$4planar))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
14	14	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or structure or pattern or recess\$3 or projection) same (substrate or wafer or web) same (drum or (cylind\$5 near9 platform\$3)) same (resist or (radiation near5 sensitive) or photoresist or photosensitive or photocur\$4)) and ((resist or photoresist or photocur\$4 or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4) and ((resist or (radiation near5 sensitive) or photoresist or photosensitive) same thick\$4 same (topograph\$4 or surface or layer or film) same (uneven or non\$4uniform or variable or vary\$4 or non\$4planar))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
15	27	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or structure or pattern or recess\$3 or projection or protuberanc\$4) same (web or (flexible near9 substrate) or (plastic near5 substrate) or (polymer\$4 near9 substrate)) same (drum or (cyлинд\$5 near9 platform\$3)) same (resin or resist or (radiation near5 sensitive) or photoresist or photosensitive or photocur\$4)) and ((resin or resist or photoresist or photocur\$4 or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4 ro cur\$4) same develop\$4) and ((translat\$4 or rotat\$4 or spin\$4 or mov\$4) same (cylindric\$4 or drum or platen) same (light\$4 or source or radiation or UV))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB



	Hits	Search Text	DBs
16	112	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or structure or pattern or recess\$3 or projection or protuberanc\$4) same (web or (flexible near12 (medium or substrate)) or (plastic near5 substrate) or (polymer\$4 near9 substrate)) same (drum or (cylind\$5 near9 platform\$3) or roll\$4) same (resin or resist or (radiation near5 sensitive) or photoresist or photosensitive or photocur\$4 or SU\$2)) and ((resin or resist or photoresist or photocur\$4 or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4 or cur\$4)) and ((translat\$4 or rotat\$4 or spin\$4 or mov\$4) same (cylindric\$4 or drum or platen or roll) same (light\$4 or source or radiation or UV)) and ((substrate or medium or wafer or web) same (foot or feet or inch\$4)) and ((expos\$4 or irradiat\$4 or cur\$4 or illuminat\$4) near22 (time or hour or minute or second))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
17	44	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or structure or pattern or recess\$3 or projection or protuberanc\$4) same (web or (flexible near12 (medium or substrate)) or (plastic near5 substrate) or (polymer\$4 near9 substrate)) same (drum or (cylind\$5 near9 platform\$3) or roll\$4) same (resin or resist or (radiation near5 sensitive) or photoresist or photosensitive or photocur\$4 or SU\$2)) and ((resin or resist or photoresist or photocur\$4 or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4 or cur\$4)) and ((translat\$4 or rotat\$4 or spin\$4 or mov\$4) same (cylindric\$4 or drum or platen or roll) same (light\$4 or source or radiation or UV)) and ((substrate or medium or wafer or web) near12 (foot or feet or inch\$4)) and ((expos\$4 or irradiat\$4 or cur\$4 or illuminat\$4) near22 (time or hour or minute or second)) and (negative same (resist or photoresist or cur\$4 or photosensitive))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
18	46	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or structure or pattern or recess\$3 or projection or protuberanc\$4) same (web or (flexible near12 (medium or substrate)) or (plastic near5 substrate) or (polymer\$4 near9 substrate)) same (area or foot or feet or (square near2 foot)) same (drum or (cylind\$5 near9 platform\$3) or roll\$4) same (resin or resist or (radiation near5 sensitive) or photoresist or photosensitive or photocur\$4 or SU\$2)) and ((resin or resist or photoresist or photocur\$4 or photosensitive) same ((expos\$4 or irradiat\$4 or illuminat\$4 or cur\$4) near26 (hour or minute)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
19	1	("4038046").PN.	US-PGPUB; USPAT

	Hits	Search Text	DBs
20	1	((microstructure or microlens\$4 or (len\$3 near6 array) or feature or structure or pattern or recess\$3 or projection or protuberanc\$4) same (web or (flexible near12 (medium or substrate)) or (plastic near5 substrate) or (polymer\$4 near9 substrate)) same (area or foot or feet or (square near2 foot)) same (drum or (cylind\$5 near9 platform\$3) or roll\$4 or conveyor) same (resin or resist or (radiation near5 sensitive) or photoresist or photosensitive or photocur\$4 or SU\$2) same ((expos\$4 or irradiat\$4 or illuminat\$4 or cur\$4) near26 hour))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB